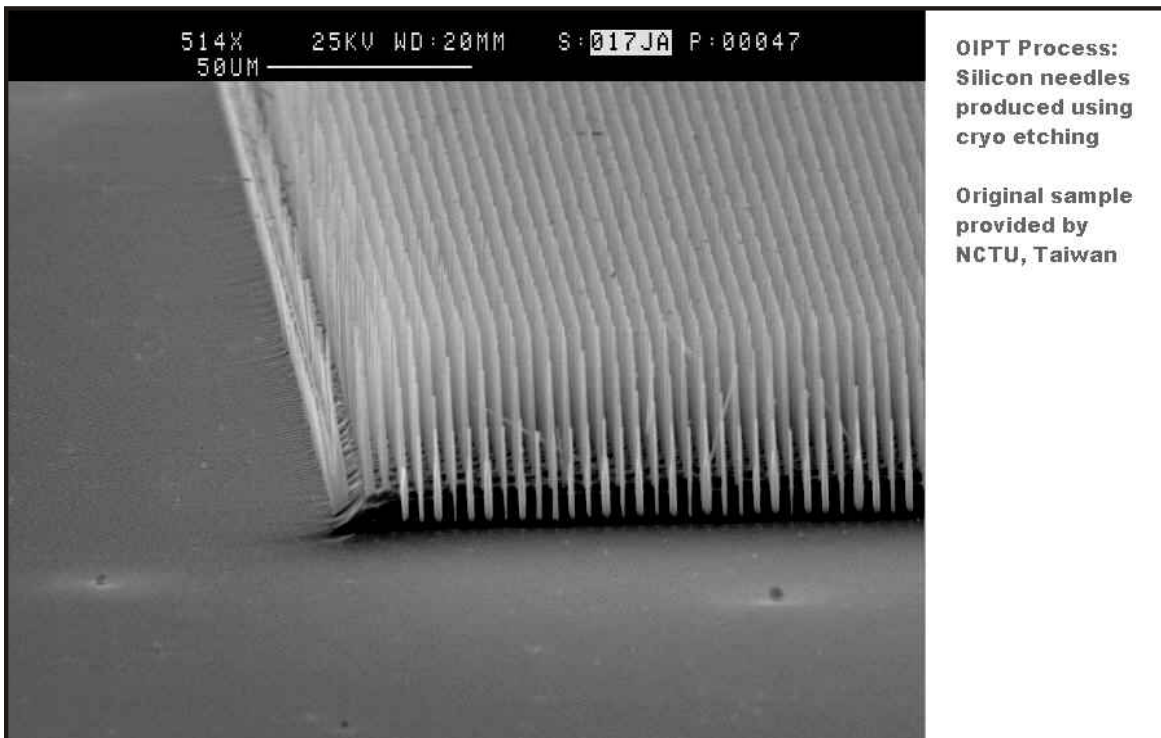


Plasmalab Data

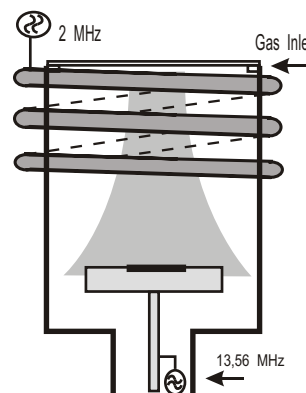
Si Needles



Plasmalab System 100
Plasmalab System 133



Plasmalab 80 Plus



Technology:

- Reactive Ion Etching
- Inductive Coupled Plasma Source
- low temperature “cryo” process
- He backside cooling

Results:

- Rate : 2.5 $\mu\text{m}/\text{min}$
- selectivity to SiO_2 150 - 350 : 1
- anisotropic etch
- controllable wall profile